Glass substrate by GWC process



Glass
Wet
Cu plating





Features

All Wet Process without Sputtering, Sol-Gel process and Courting

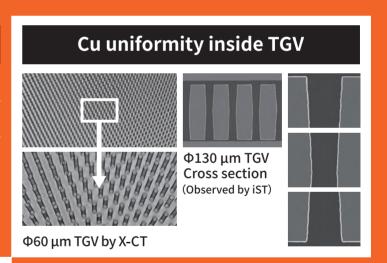
Direct Cu Plating on Glass without Intermediate Layer (Ti, Cr etc.)

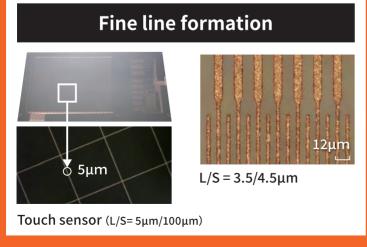
Smooth and Transparency without Glass Surface Etching

Stable Adhesion Strength Peel strength about 0.4 ~ 0.8 kN/m

Excellent Cu film Uniformity inside TGV Applicable to TGV until A.R. 20

Peeling test Adhesion strength		
Non Alkaline	0.8 kN/m	
Borosilicate	0.5 kN/m	
Quartz	0.4 kN/m	





mass product accommodate size		
Glass Type	Soda, Non-Alkaline Borosilicate, Quartz	
Shape, Size	Wafer	Φ 4, 6, 8, 12 inch
	Panel	\leq 515 \times 510 mm (available in the near future)
TGV	Size	$\geqq \Phi 5 \mu m$ (available in the near future)
	A.R.	≦ 20



